

| | Hits | Search Text | DBs |
|----|------|---|--|
| 34 | 29 | ((resist or photoresist)) and (resin\$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (non\$4ionic or cationic or anionic or amphoteric)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 35 | 31 | ((resist or photoresist)) and (resin\$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (non\$4ionic or cationic or anionic or amphoteric or polyoxyalkylene or polyoxyethylene)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |
| 36 | 24 | ((resist or photoresist) same pattern) and (resin\$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (non\$4ionic or cationic or anionic or amphoteric or polyoxyalkylene or polyoxyethylene)) | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |